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PROSECUTION OF THE SUBJECT APPLICATION

Applicant: N.B. Cobb Attorney Docket No. MEGC121783  
 Application No.: 10/696,276 Group Art Unit: 2123  
 Filed: October 29, 2003  
 Title: METHOD AND APPARATUS FOR PERFORMING OPC USING MODEL CURVATURE

U.S. PATENT DOCUMENTS

*Examiner Cite	Kind	Date			
Initials No. Document No. Code (mm/dd/yyyy) Name					
JO U1	5,815,685	A	09/29/1998	Kamon	
U2	5,825,647	A	10/20/1998	Tsudaka	
U3	6,033,814	A	03/07/2000	Burdorf et al.	
U4	6,080,527	A	06/27/2000	Huang et al.	
U5	6,120,952	A	09/19/2000	Pierrat et al.	
U6	6,226,781	B1	05/01/2001	Nistler et al.	
U7	6,249,904	A	06/19/2001	Cobb	
U8	6,269,472	A	07/31/2001	Garza et al.	
U9	6,301,697	A	10/09/2001	Cobb	
U10	6,312,854	A	11/06/2001	Chen et al.	
U11	6,370,679	A	04/09/2002	Chang et al.	

FOREIGN PATENT DOCUMENTS

*Examiner Cite	Kind	Publication Date	Country	English	Abstract	Translation
Initial No. Document No. Code (mm/dd/yyyy)				Provided	Provided	Provided
None						

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OTHER INFORMATION  
(Including Author, Title, Date, Pertinent Pages, Etc.)

*Examiner Initial	Cite No.	
<u>JO</u>	O1	Cobb, N., et al., "Experimental Results on Optical Proximity Correction with Variable Threshold Resist Model," <i>Optical Microlithography X, The International Society for Optical Engineering 3051</i> :458-468, March 1997.
<u>JO</u>	O2	Cobb, N.B., "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing," Ph.D. dissertation, University of California at Berkeley, Spring 1988, pp. 64-71.
<u>JO</u>	O3	Cobb, N., et al., "Mathematical and CAD Framework for Proximity Correction," <i>Optical Microlithography IX, The International Society for Optical Engineering 2726</i> : 208-222, March 1996.
<u>JO</u>	O4	Benchmark Technologies, OPC Reference Standard (J111A) Reticle, October 12, 1999.
<u>JO</u>	O5	"Resolution Enhancement Technologies (OPC/PSM)," July 16, 2002, Mentor Graphics Internet Site, Technical Papers.
<u>JO</u>	O6	Randall, J., et al., "Lithography Simulation With Aerial Image - Variable Threshold Resist Model," <i>International Conference on Micro and Nano Engineering 46</i> :59-60, September 1998.
<u>JO</u>	O7	Rieger, M.L. and J.P. Stirniman, "Using Behavior Modeling for Proximity Correction," <i>SPIE Proceedings, The International Society for Optical Engineering, Optical/Laser Microlithography VII 2197</i> :371-376, May 1994.
<u>JO</u>	O8	Schellenberg, F.M., et al., "SEMATECH J111 Project: OPC Validation," <i>SPIE Proceedings, Optical Microlithography XI 3334</i> :892-911, 1998.
<u>JO</u>	O9	Schellenberg, F.M., "Design for Manufacturing in the Semiconductor Industry: The Litho/Design Workshops," <i>Proceedings of the 12th Int'l. Conference on VLSI Design</i> , Jan. 10-13, 1999, pp. 111-119.
<u>JO</u>	O10	Schellenberg, F.M., "Sub-Wavelength Lithography Using OPC," <i>Semiconductor Fabtech</i> , 9th ed., March 1999.
<u>JO</u>	O11	Spence, C., et al., "Integration of Optical Proximity Correction Strategies in Strong Phase Shifters Design for Poly-Gate Layers," <i>SPIE Proceedings, 19th Annual Symposium of Photomask Technology 3873</i> :277-287, 1999.

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3873:21, Editors: Abboud, F. et al., 1999.~~

~~O13 SPIE Proceedings, Optical Microlithography IX 2726:15, Editors: Fuller, G.E.  
et al., 1996.~~

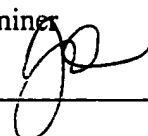
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O14 Stirniman, J.P. and M.L. Rieger, "Optimizing Proximity Correction for Wafer  
Fabrication Processes," *Proc. SPIE, 14th Annual BACUS Symposium on  
Photomask Technology and Management* 2322:239-246, December 1994.

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O15 Washington, A., *Basic Technical Mathematics with Calculus*, 2d ed., 1970,  
pp. 245-247, 260-262, 505-525.

Examiner



Date Considered

11/06/06

\*Examiner: Initial if reference considered, whether or not citation is in conformance with  
M.P.E.P. § 609; draw line through citation if not in conformance and not considered. Include  
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